

Supplementary Information

**Layer-number-dependent Photoswitchability in 2D MoS<sub>2</sub>-Diarylethene Hybrids**

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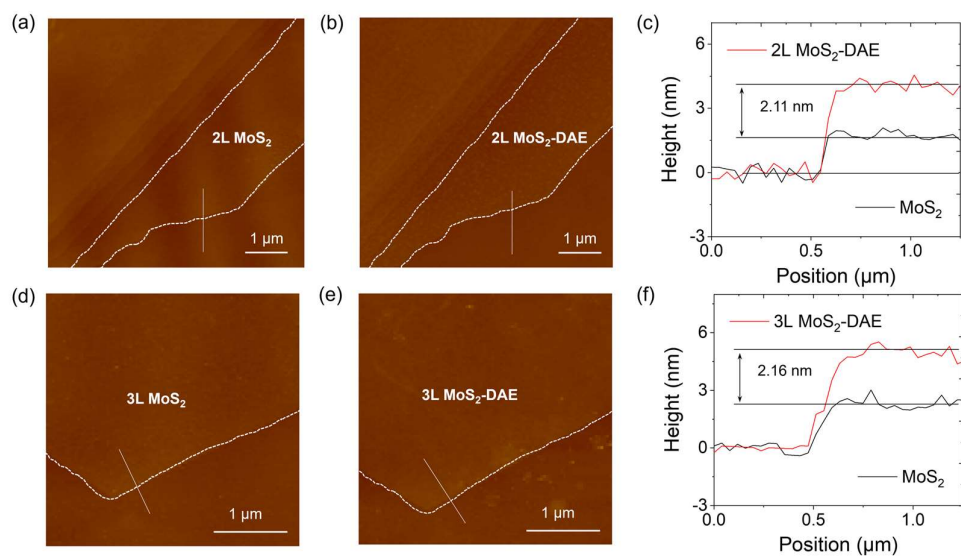
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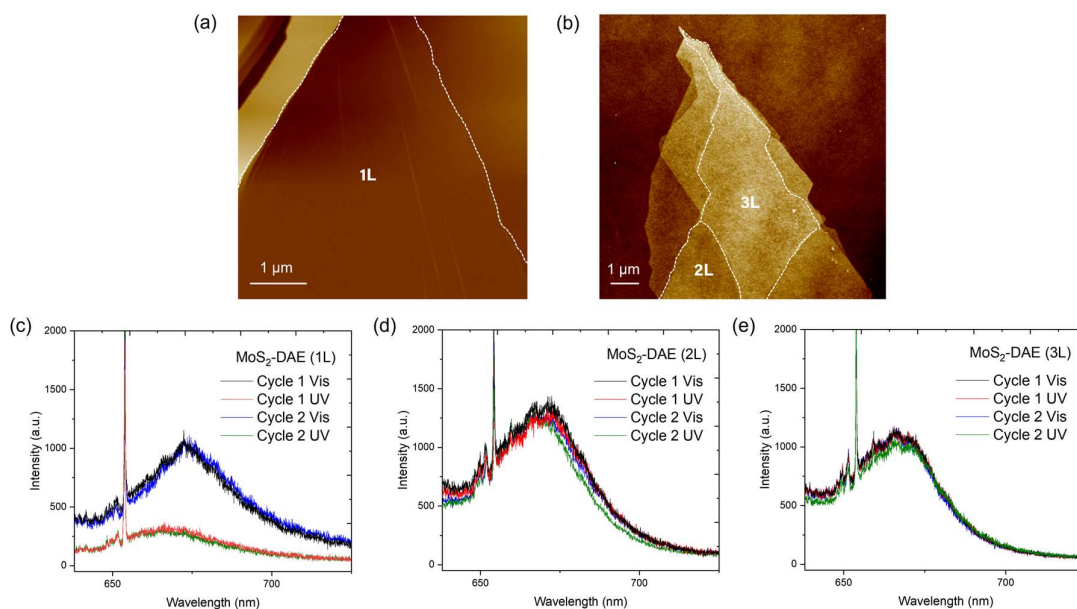
1. AFM Imaging of MoS<sub>2</sub>-DAE Samples on SiO<sub>2</sub>/Si Substrates
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## 1. AFM Imaging of MoS<sub>2</sub>-DAE Samples on SiO<sub>2</sub>/Si Substrates



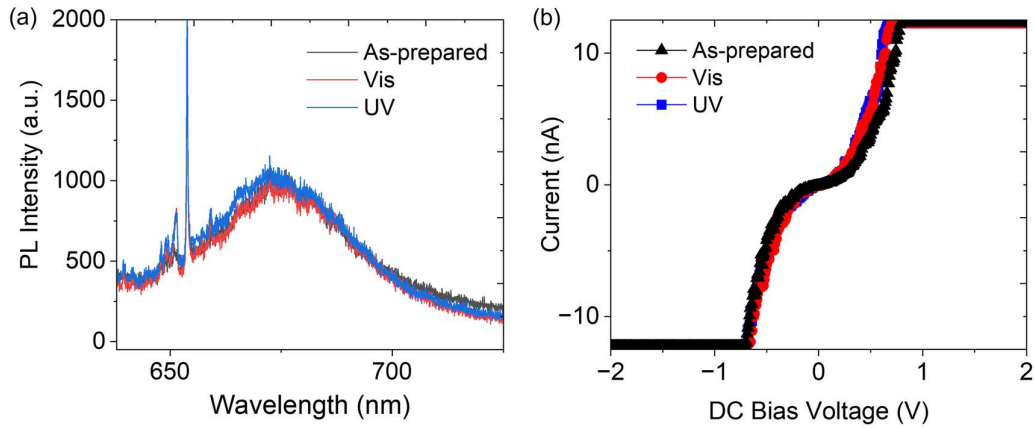
**Figure S1.** AFM images of (a) 2L MoS<sub>2</sub> flake and (b) 2L MoS<sub>2</sub>-DAE hybrid are shown, with the corresponding height differences depicted in (c). The thickness of the 2L MoS<sub>2</sub> flake is ~1.60 nm, while the DAE measures ~2.11 nm. Additionally, AFM images of (d) 3L MoS<sub>2</sub> flake and (e) 3L MoS<sub>2</sub>-DAE hybrid are provided. The thickness of the 3L MoS<sub>2</sub> flake is ~2.28 nm, and the DAE measures ~2.16 nm. These samples were used for PL measurements presented in Figure 2e-f.

## 2. PL Measurements of Additional MoS<sub>2</sub>-DAE Hybrid Samples



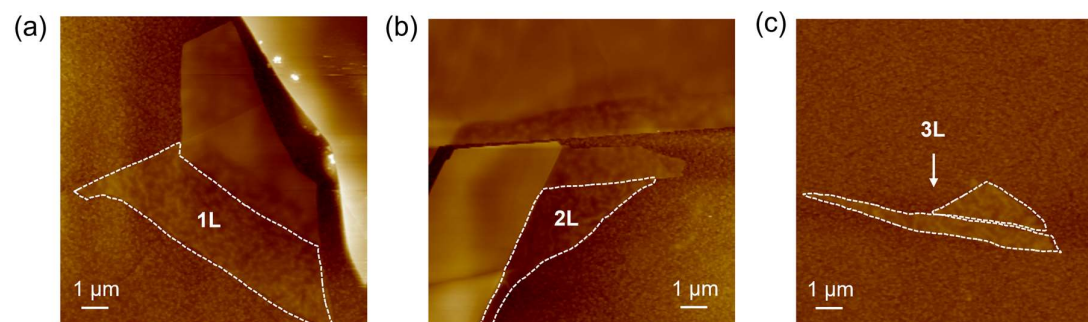
**Figure S2.** AFM image of MoS<sub>2</sub> flakes featuring (a) 1L, (b) 2L, and 3L, with the boundaries highlighted by dotted lines. The photo-modulation processes were repeated twice on the 1L to 3L MoS<sub>2</sub>-DAE system. (c) The 1L MoS<sub>2</sub> exhibits significant PL quenching after UV irradiation, with the signal fully recovering under visible light. In contrast, the hybrids with (d) 2L and (e) 3L MoS<sub>2</sub> show no notable PL quenching.

### 3. Control Experiments with Monolayer MoS<sub>2</sub>



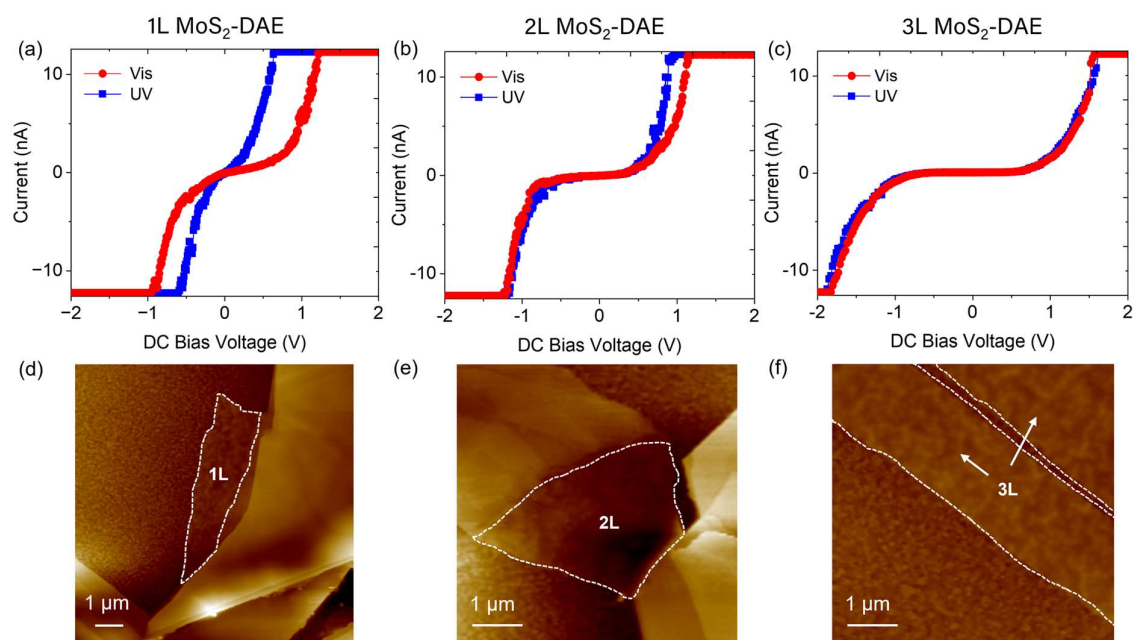
**Figure S3.** Control experiments were conducted with 1L MoS<sub>2</sub> (without a DAE layer) to confirm the effects of visible and UV light irradiation, which also indicates minimal substrate effects on charge transfer interactions. (a) The PL emission of as-prepared monolayer MoS<sub>2</sub> is consistent with those after exposure to visible and UV irradiation, showing no significant differences. (b) The C-AFM results also indicate that the variations between each case are minimal. These results indicate that optical modulation in the 1L MoS<sub>2</sub>-DAE system arises from the unique hybrid interaction between DAE and 1L MoS<sub>2</sub>.

#### 4. AFM Imaging of MoS<sub>2</sub> Samples on ITO Substrates



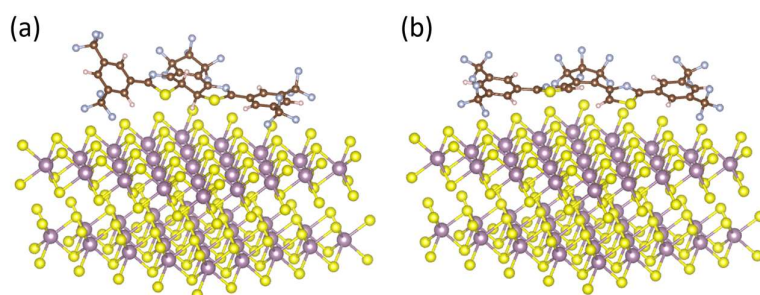
**Figure S4.** AFM images of (a) 1L MoS<sub>2</sub>, (b) 2L MoS<sub>2</sub>, and (c) 3L MoS<sub>2</sub> flakes fabricated on ITO substrates. These samples were used to measure C-AFM data presented in Figure 4.

## 5. C-AFM Measurements of Additional MoS<sub>2</sub>-DAE Hybrid Samples



**Figure S5.** Additional C-AFM measurements were conducted on MoS<sub>2</sub>-DAE hybrid samples under both visible and UV light irradiation. These measurements were performed on (a) 1L MoS<sub>2</sub>, as illustrated in the AFM image (d); (b) 2L MoS<sub>2</sub>, as depicted in the AFM image (e); and (c) 3L MoS<sub>2</sub>, as shown in the AFM image (f).

## 6. DFT Calculations



**Figure S6.** Representative relaxed hybrid structures. (a) Closed- and (b) Open-form DAE on 2L MoS<sub>2</sub>-DAE. The DAE conformation and interaction at the hybrid heterointerface are consistent with those between DAE and 1L and 3L MoS<sub>2</sub>.